







ZURICH, SEPTEMBER 3 – 7

Please visit our website for updated information **www.ICCCS2012.ethz.ch**

3rd Announcement and Session Program

Clean Technologies – What is the Future?







Zurich, Switzerland
September 3 - 7, 2012
Swiss Federal Institute of Technology ETH Zürich
www.ICCCS2012.ethz.ch



Chairman's Welcome



It is a great honor for the Swiss Contamination Control Society, SwissCCS (SRRT). to host the 21st International Symposium on Contamination Control, ICCCS 2012, at the ETH, the reputable Swiss Federal Institute of Technology in Zurich, Switzerland.

Zurich has been the city where the International Confederation of Contamination Control Societies, ICCCS, was founded in 1972 and the first international meeting was held. In 1990 Switzerland hosted the 10th International Symposium and 22 years later, in 2012, we are proud to invite again to Zurich to meet at the ETH for a productive exchange of vast experience, know-how, and to enjoy friendship throughout all the participating countries.

Latest advances in cleanroom technology, control of particulate and molecular contamination, as well as new fascinating applications, such as nanotechnology, are challenges of the future. Innovative approaches, applications, and ideas, as well as technology to reduce the risk of accidents will be discussed at the symposium.

We invite you to get together at the 21st ICCCS Symposium in the wonderful City of Zurich. An attractive partner program, visits to interesting companies, exhibitions, and a banquet will accompany the visionary technical program. Outstanding keynote speakers will present their view on advanced subjects and future trends. In addition, many working groups and committees will hold their meetings during the Symposium week.

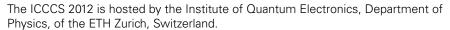
On behalf of the SwissCCS and of the whole organizing committee we welcome you to Zurich and are looking forward to seeing you at the symposium. Sincerely,

Hans Zingre, Chairman ICCCS 2012 President SwissCCS

Professor Jérôme Faist, ETH Host, Quantum Optoelectronics Group, Department of Physics, ETH Zurich

Organizers







It is organized by SwissCCS, the Swiss Contamination Control Society for ICCCS, the International Confederation of Contamination Control Societies.

Scientific and Organizing Committee

Symposium Chairman: Hans Zingre, President SwissCCS

Members: Arnold Brunner Switzerland Egon Holländer Switzerland Tobias Merseburger

Switzerland Norbert Otto Germany Alexandra Stärk Switzerland Werner Straub Switzerland

Switzerland

Secretary ICCCS 2012: Alfred Moser, Science Services Switzerland

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Da Qian Wang	CCCS International Coop Dept., Beijing	China		
Jing Wang	ETH Zurich	Switzerland		
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ICCCS Member Societies



Austria ORRG Ireland ICS Brazil SBCC Italy ASCCA China CCCS Japan JACA Egypt ECCCS Korea KACA France ASPEC

Nordic Countries R3 Nordic

Germany VDICCT Romania RACC Russia ASENMCO Scotland S2C2 Switzerland SwissCCS The Netherlands VCCN **USA IEST**

Please, find more information about the International Confederation of Contamination Control Societies, ICCCS, on its web site: http://icccs.net/





Topic

Facilities

Standardization

Research and development

Metrology

Environmental control

Equipment

Health care

Life sciences

Cleaning & services, Surface cleanliness

Filtration

Nanotechnology

VOC contamination

GMP: Good Manufacturing Practices
HACCP: Hazard Analysis and Critical Control Point

HAZOP: Hazard and Operability

Examples

New trends in cleanroom engineering design,

physical parameters

New and revised standards (chemical and

particle cleanliness of surfaces, nanotechnology), etc.

New technology trends

New instruments and methods, monitoring,

statistics

Concepts, energy, material, and waste management,

regulations, methods, etc.

Equipment, automation, robotics, energy

management, building technology,

infrastructure, etc.

Medical devices, health care, hygiene

Pharmaceutical industry, food industry,

GMP, HACCP, HAZOP, etc.

Material compatibility, efficiency, methods, etc.

Particle-, chemical-nano filtration, minienvironments, isolators, RABS, etc.

Tillienvironinents, isolators, NADS, etc.

New challenges for contamination control in nanotechnology applications, nanoparticles,

atomic layer deposition

Volatile organic compounds and contamination, material emissions, decomposition of VOCs, standardized procedure for monitoring

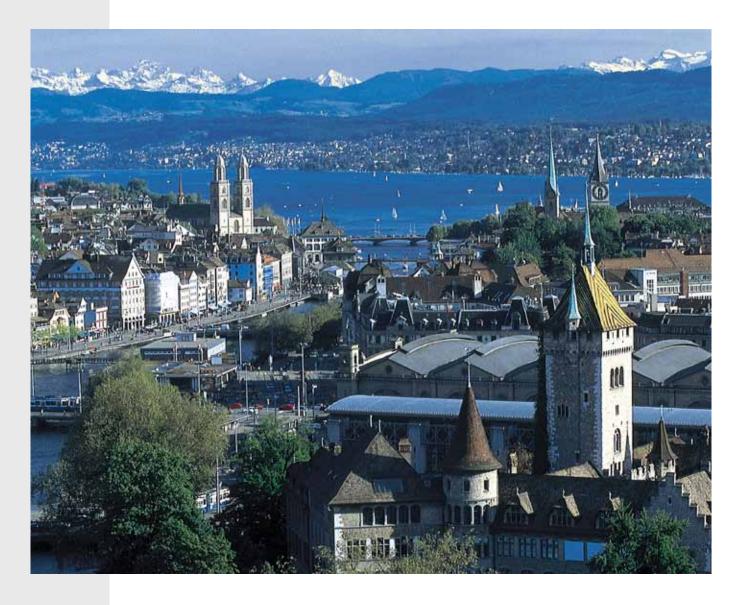
RABS: Restricted Access Barrier Systems



Important Dates, Calendar

Book accommodation before	2012
Regular registration deadline	
Conference registration desk	
Comercine registration acsi	[[1]]]]]

Book accommodation before:	July 31, 2012	
Regular registration deadline:	August 17, 2012	
Conference registration desk opens at 15:00	September 3, 2012	









ICCCS 2012 Session Program



Program with technical sessions, keynote plenary lectures, and technical tours.

	Septe	ember 3,	2012	Septe	ember 4,	2012	September 5, 2012		September 6, 2012		September 7		ber 7		
8:00	ı	Monday	1	-	Tuesday	y	Wednesday		Thursday		Friday				
9:00	9:00				egistration Ke ML E 13 Roland		eynote 2 nd Germann		Keynote 3 Sylvain Cottens		likon	rthur			
					Break			Break			Break		sch		nte
				Opening, Welcome		ies	se ess	ogy	ogy on on on		3ue		. <u>«</u>		
10:00		(RT)		Keynote 1 Udo Gommel		Facilities physical	Surface cleanliness	Metrology	Nano technology Filtration Control		M Lab, I		I Tour 2: GmbH, Winterthur		
		(FA R		Break	& Exhi	bition	Break	& Exhi	bition	Break & Exhibition		1: IB	1: IB		
11:00 12:00		VDI Fachausschuss Reinraumtechnik (FA RRT)	ICEB Meeting	Facilities general	Surface cleanliness	Health care	Standardization	Research & development	Metrology	Nano technology	Filtration	Equipment	Technical Tour 1: IBM Lab, Rueschlikon	Departure and return times and location of bus pick-up will be announced I	Technical Zimmer Orthopedics
40.00		ausschuss					Ö			Closing Session Close at 13:30 Farewell Lunch		sion	2	tion of bus	Z
13:00		Fach	당χ	Lu	nch Bre	eak	Lu	nch Bre	eak			3:30	ur d loca		
		VDI	Lunch Break											terth	
14:00				sign	« ه (۱	<u>e</u>	ation	tion	sec			ınch	2: H, Win		Rues
15:00			ICCCS CoD Meeting	Facilities design	Cleaning & services	Health care	Standardization	VOC contamination	Life sciences				Technical Tour 2: hopedics GmbH,	eparture and	: IBM Lab,
	Regist	ration	S CoD	_	& Exhi	bition		& Exhi	bition				Techi	Techr hope	
16:00	at entra Dozente)))	es design	Cleaning & services	Ith care	ardization	VOC contamination	sciences				Technical Tour 2: Zimmer Orthopedics GmbH, Winterthur		echnical Tour 1: IBM Lab, Rueschlikon
17:00				Faciliti	Clea	Неа	Standa	conta	Life s				7		
18:00	Doz	elcome Party, ozentenfoyer, Main Building HG, Floor J Exhibition Exhibition		on											
19:00				Ses	ssion C Dinner		at I	quet Di Restaur ake Sid	ant						
20:00															

Tuesday, Sep. 4, 2012	
Room: D	
Keynote 1	9:50
Udo Gommel: A short Introduction to Cleanliness Technology: Meeting the future Challenges	4011
Room: A	
Facilities general	11:00
Joao Ramos: Indoor Air Quality Audit of Office Buildings in Portugal	4111
Frank Hochmair: Fast Track Cleanroom	4112
Thomas Lederer: Retrofit of existing facility	4113
Facilities design	14:00
SHOJI TAIZO: The new airflow system for cleanliness and temperature stability	4211
Xiaofeng Cheng: Research progress on contamination control technology of Shenguang-III Laser Facility	4212
Ondrej Pech: Capture efficiency of pollutants in a free space and over a workbench with reinforced slot exhaust systems	s 4213
Facilities design	16:00
André Bösiger: From Conceptual Design to Validated Equipment "Suppliers View"	4311
Kwang-Chul Noh: Application of partition in LCD clean room for cross contamination control	4312
Frans Saurwalt: The cascade approach: segregation by airflow design in stead of by room pressure.	4313
Room: B	
Surface cleanliness	11:00
Yoshihiko Yajima: Introduction of Surface Particle Counter	4121
Xiaodong Yuan: Laser Cleaning of the Contamination on the Surface of Optics and Sandstones	4122
Kae Sasaki: Optical Measurement of Particles diameter and refractive index on the Glass Surface by Light-Scattering	4123
Cleaning & services	14:00
Berit Reinmüller: Clothing systems in Operating rooms – a comparative study	4221
Joachim Ludwig: Cleaning and packaging of single parts and components for the use under clean room conditions	4222
Cleaning & services	16:00
Frank Duvernell: Risk management for a professional Cleanroom Cleaning	4321
Frank Duvernell: significance of gowning procedures	4322
Shiue Angus: Dynamic measurement of particle production rate of an operator with different garment arrangement in Cleanrooms	4323
Room: C	
Health care	11:00
Bengt Ljungqvist: Swedish survey and a summary of investigations in operating rooms	4131

Jan Gustén: Dispersion of airborne contaminants through door openings in operating rooms	4132
Benoit Sicre: Mobile instrument tables with laminar air flow for protection against contamination in operation theatres: assessment of effectiveness	4133
Health care	14:00
Zhecho Dimitrov Bolashikov: Reduced exposure to coughed air by a novel ventilation method for hospital patient rooms	4231
Stefanie Rud: Photo sensitization, an innovative Technology for Cleanrooms and Environments with high standards of hygienic	4232
Lu Yang: Study on Ventilation Strategy for Removing Dust Particles	4233
Health care	16:00
Horst Weisssieker: Green Blue Yellow Hospital	4331
Leander Mölter: Determination of the protection degree according to SWKI 99-3 and DIN 1946-4	4332
Jihong Ling: Research on Air Distribution and Air Changes in Airborne Infection Isolation Room	4333
Wednesday, Sep. 5, 2012	
Room: D	
Keynote 2	8:30
Roland Germann: Nanotechnology for the Computer Industry	5011
Room: A	
Room: A Facilities physical	9:30
	9:30 5111
Facilities physical	
Facilities physical Martin Pesek: The temperature fields measurement method in the air in small closed spaces using an infrared camera	5111
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Facilities physical Martin Pesek: The temperature fields measurement method in the air in small closed spaces using an infrared camera Christian Schmidt: A New Challenge for High-Tech Fab/Lab Design – Control of Electromagnetic Fields Standardization Egon Hollaender: Cleanrooms and Contamination Control: Changes and new tendencies in the standardization Dr. A. Fedotov: CLEANROOM STANDARDIZATION: WHERE DOES IT GO? A. Fedotov: New method of cleanroom classification with assurance factor Standardization Werner Straub: Classification Clean Surfaces R Vijayakumar: Global Standard for HEPA and ULPA Filter Testing and Classification Philip van Beek: Compliance is the new C	5111 5112 11:00 5211 5212 5213 14:00 5311 5312 5313
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Room: B	
Surface cleanliness	9:30
Isabelle Pecault: Performance assessment of probes dedicated to the monitoring of surface particle contamination	5121
Isabelle Pecault: Analysis of intentional organic contamination adsorbed on optics in a dedicated microchamber and impact on the optics performance.	5122
Research & development	11:00
KYUNG-HOON YOO: Comparative Study on Energy Consumption in Steam-Humidification- and Water-Spray- Humidification-Type Outdoor Air-Conditioning Systems for Semiconductor Manufacturing Clean Rooms	5221
Jihun Mun: Theoretical analysis and quantitative evaluation of particle measurement probability in light scattering sensor system to solve uncertainty problem	5222
Tadashi Okada: Stochastic study of aerosol contamination detection from time variation in aerosol number concentration in real time	5223
KYUNG-HOON YOO: An Experimental Study on Energy Consumption in Air Washer Outdoor Air Conditioning Systems for Semiconductor Manufacturing Clean Rooms	5224
VOC contamination	14:00
Yuiko Yamane: Secondary organic aerosol formation from p-Dichlorobenzene in the indoor air	5321
K. Sekiguchi: Simultaneous decomposition of O3 and VOC with an ozone-decomposition catalyst immobilized on a nonwoven fabric	5322
Sumin Kim: Application of tannin resin as novel environment-friendly adhesion system for particle boards	5323
Norikazu Namiki: Attempts to verify mechanisms for ultrafine particle generation from laser printers	5324
VOC contamination	16:00
Markus Keller: Classification of volatile organic contamination from cleanroom materials: VDI 2083 part 17	5421
Shiue Angus: Monitoring and Analyzing Volatile Organic Compounds in Fabs by Gas Chromatograph / Surface Acoustic Wave sensors	5422
T. Yoshida: Complete decomposition of water-soluble VOC using ozone microbubbles and TiO2 photocatalyst immobilized on a nonwoven fabric	5423
Room: C	
Metrology	9:30
Koos Agricola: Determination of operational quality of cleanroom by particle deposition monitoring	5131
Gordon Farquharson: New real space technique for visualisation and counting of fine airborne particles	5132
Metrology	11:00
sang gu Lee: Application and performance test of a wide-range particulate matter sensor for real-time measurements	5231
Jürg Schlatter: Independent calibration for optical particle counters	5232
Sheng xiong REN: Analysis and discussion of recovery time measure method	5233
Life sciences	14:00
Hans Zingre: Detection of Microorganisms in Compressed Gases	5331
Beat Glauser: A new Method for Continuous Measurement of Air Born Biological Contamination in Isolators and RABS Systems	5332
Esmeralda Carvalho: Alternative solution for aero-biocontamination control in clean rooms in few hours	5333
Life sciences	16:00
Alexander Fedotov: AIR CLEANLINESS FOR STERILE PRODUCTION	5431
Vincent Thomas: An updated review of VHP efficacy and mechanism of action	5432
Silvia Yuko Eguchi: Effect of support material on biocide concentration required for Biofilm eradication	5433

Thursday, Sep. 6, 2012	
Room: D	
Keynote 3	8:30
Sylvain Cottens: Emerging technologies in drug discovery	6011
Room: A	
Nanotechnology	9:30
Jing Wang: Filtration of airborne nanoparticles down to single-digit nanometer range	6111
Kyu-Tae Park: Fabrication of carbon nanotube-deposited air filter using aerosol and thermal CVD processes and its use for the enhancement of nano-particle filtration and inactivation of bioaerosols	6112
Nanotechnology	11:00
KYUNG-HOON YOO: Particle-Free Atomic Layer Deposition of Transparent Conductive Oxide for Flexible Organic Solar Cell	6211
Taesung Kim: In situ size measurement and analysis of Si Nanoparticles using PBMS	6212
Room: B	
Filtration	9:30
Michael W. Osborne Ph.D.: Applied membrane air filtration technology for best energy savings and enhanced performance of critical processes	6121
Junho Hyun: Optimization of particle filtration system assisted by electrostatic force using week electric field and carbon brush ionizer	6122
Filtration	11:00
R Vijayakumar: Filter Test Methods Using Sodium Flame Photometer and Particle Counters	6221
Jens Mueller: AMC control and state of the technology filters in the semiconductor industry	6222
Christopher Muller: Advanced AMC Control for Leading-Edge Microelectronics Manufacturing	6223
Room: C	
Environmental control	9:30
Jianping Jiang: Real time microbial detection by laser induced spectroscopy and its application in contamination control	6131
Robert Laudien: Continuous emission monitoring of ammonia by ion mobility spectrometry with a non-radioactive ionization source	6132
Equipment	11:00
Leander Mölter: Calibration system for optical particle counters	6231
Takuya Kambayashi: Tornado nozzle for vacuum cleaning	6232
You-haeng Joe : Production and evaluation of a ubiquitous sensor network dust sensor for monitoring aerosol concentration in the flow duct	6233







Various task and working groups will hold meetings during the ICCCS 2012 Symposium. A tentative schedule for the group meetings is shown below. Capital letters G, H, J, K refer to different meeting rooms. Werner Straub of the ICCCS 2012 Organizing Committee coordinates the group and committee meetings. Chairmen can report changes in their group meetings to him. The schedule may still change at any time. Updates will be published on http://www.icccs2012.ethz.ch/groups.

Group name	Date	Morning, a.m.	Afternoon, p.m.
VDI Fachausschuss Reinraumtechnik (FA RRT)	Sep 3, 2012	Н	
ICEB Meeting	Sep 3, 2012	J	
ICCCS CoD Meeting	Sep 3, 2012		J
ISO TC142 WG s	Several WG mee	tings from Monday to T	hursday, Sep. 3-6
ISO TC142 Plenary Meeting	Sep 7, 2012	J	J
ISO TC209 WG 1	Sep 6, 7 & 8, 2012	Н	Н
ISO TC209 WG 3	Sep 7 & 8, 2012	G	G
ISO TC209 WG 10	Sep 8, 2012	K , pending	K , pending
ISO TC 209 Technical Committee	Sep 10, 2012 Sep 11, to 14:00	Н	Н
CEN TC195 WG6 - M/461	Sep 5, 2012	J	
CEN TC 243, Cleanrooms	Sep 11, 2012		Н
DIN Assessment of suitability of equipment and materials for cleanrooms			

Entries G, H, J, K are meeting room names.

This tentative schedule may change at any time. Updates on http://www.icccs2012.ethz.ch/groups





IBM Research – Zurich is one of nine IBM research laboratories around the globe. The Zurich laboratory in Rueschlikon was established in 1956. Cutting-edge research and outstanding scientific achievements – most remarkably two Nobel Prizes – are associated with this lab. One of them for scanning tunneling microscope (Binning, Rohrer) opened the era of nanotechnology. As the European branch of IBM Research, the mission of the IBM Research – Zurich lab – in addition to pursuing advanced research for tomorrow's information technology – is to be one of the premier places to work for world-class researchers and to help drive Europe's innovation agenda. - http://www.zurich.ibm.com/

In 2011, a new facility for collaborative nano-scale research was opened on the campus of IBM Research – Zurich. The Nanotechnology Center is part of a strategic partnership in nanotechnology with ETH Zurich.

The visit at IBM Research – Zurich on Friday, September 7, 2012, is organized in two groups, one in the morning, the other in the early afternoon. In identical tours, the groups will visit the IBM Industry Solutions Lab. After an overview, the current research in nano technology is introduced, and a tour through different labs and/or showrooms concludes the visit.

Technical Tour to Zimmer Orthopedics GmbH, Winterthur



Zimmer Orthopedics Switzerland GmbH in Winterthur is an international leader in development, production, and marketing of the highest quality orthopaedic surgical products (OSP) and services that repair, replace and regenerate. We'll get a chance to have a glimpse at research and development of human implants for surgical repair. Hip, knee, elbow, shoulder, spine, and trauma products are manufactured in the Winterthur, Switzerland, Facility. These are also the European headquarters.



Each of these tours takes only half a day and will be conducted twice, so delegates can book both, one in the morning and one in the afternoon. The number of participants is limited. Participation must be specified on the symposium registration. Departure time and location of shuttle bus will be communicated to registered participants.

Sightseeing Tours for Accompanying Persons



Sightseeing tours for accompanying persons are planned for Tuesday, September 4 (old town of Zurich) and Wednesday, September 5, 2012 (full-day excursion to Swiss Alps and a morning excursion to Chocolate manufacturer Frey). Details and cost are on Symposium web site.

See our Webpage: http://www.icccs2012.ethz.ch/sightseeing

Tuesday, September 4, 2012 - Walking tours in Zurich

- Stories of the Old Town Rediscover Zurich historic center. Time: 10:00 a.m.
- From Calatrava to Gull Impressive architecture Time. Time: 13:30
- Zürich & Its Guilds Stories and traditions. Time: 16:00

Wednesday, September 5, 2012 - Full-day excursions

- Day excursion to Appenzell and Saentis peak. Time: 08:00 17:00
- Day excursion to Lucerne & Pilatus peak. Time: 08:00 17:00
- Morning excursion to Chocolate manufacturer Frey. Time: 08:00 13:00



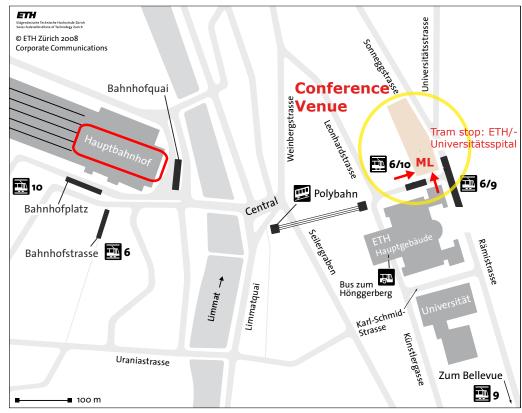


Conference Venue: ETH Zurich, Switzerland

The ICCCS 2012 will be held at the ETH in Zurich, September 3-7, 2012. The ETH is the Swiss Federal Institute of Technology , www.ethz.ch/index_EN. The symposium takes place in the Mechanical Engineering Department Building ML (Maschinenlaboratorium) in the original campus in the center of town. It is easy to get there from the main train station (Hauptbahnhof, HB) of Zurich by tram nos. 6 or 10 or by walking. Please, consult the following map:

City Map







Mechanical Engineering Department Building ML (Maschinenlaboratorium)



The Mechanical Engineering Department Building ML is also visible in the aerial view at right of the historic main building.



Book flights to Zurich International Airport (ZRH). How to reach Zurich Main Station by train

The transfer from the airport train station to the center of Zurich (Main Station, Hauptbahnhof HB) takes only about 12 min, and trains operate frequently. Please, buy a ticket at the vending machine (with credit card) or at the ticket counter on the floor above the tracks before you board the train.

Other travel options are on http://www.icccs2012.ethz.ch/travel





Zurich – World Class, Swiss Made®

As a lifestyle capital on the water, Zurich offers the unique mix of discovery, pleasure, nature and culture. The finest culinary highlights, unlimited shopping pleasure, over 50 museums and more than 100 galleries, Switzerland's liveliest nightlife, numerous events and countless green oases in the center of the city tempt guests to linger and enjoy.



Please, visit the web site of Zurich Tourism to get information on sightseeing, accommodation, excursions, gastronomy, nightlife, and much more! – http://www.zuerich.com/en/Visitor.html

Travel Information:

www.zuerich.com/en/Meeting-Convention/Planning/Congress-Transportation.html



Symposium Registration



Registration is simple. To be able to submit an abstract, you have to open an account on the ICCCS-2012 server. This is not a conference registration, it just identifies you as an author and/or potential participant. For instructions, please consult the flowchart on http://www.icccs2012.ethz.ch/Registration/Guideline.

To make a valid conference registration, go to the Registration page and select Conference registration. At this time you must use your credit card to pay for registration. The Credit-card interface uses a secure connection. Regular registration deadline is August 17, 2012. Please note that you are not automatically registered when you submit an abstract and paper! Like all symposium participants, authors also have to register.

A separate registration must be submitted for accompanying persons (using the same Login Account). Accompanying persons are spouses or partners of delegates; they have no access to technical presentations.

Registration Fees



- Full participant (including banquet dinner)
 Student (including Banquet dinner)
 Accompanying person (Banquet dinner)
 Speaker (first author only, including banquet dinner)
 CHF 750
- Technical tour: Program and cost on symposium web site.
- Sightseeing tour for accompanying persons: Details and cost on symposium web site.
- Currency of Fee: CHF (Swiss Francs)

Cancellation Policy



For cancellation of a paid registration for any reason after August 5, 2012, no refund can be paid. The full registration fee is forfeited. In case of a cancellation of a paid registration on or before August 5, 2012, 50% of the amount received by the conference office (minus bank fees) will be refunded on request.





Accommodation in Zurich

Reservation and booking of hotel rooms must be done by conference attendees themselves independently of symposium registration. Payment for accommodation is settled directly with the hotel. We have published a list of recommended hotels on the Symposium web site: www.icccs2012.ethz.ch/travel/accommodation.

The hotels with blocks of rooms reserved by Zurich Tourism:

Zürich Marriott Hotel *****
Hotel Krone Unterstrass ****
Hotel Alexander ***
Comfort Hotel Royal ***
Hotel Astor ***
Walhalla Hotel ***
Zürcherhof, Best Western Hotel ***
Hotel Limmathof **
Hotel Marta **

On www.zuerich.com/en/hotels/ you will find a city map with the locations of hotels, their categories (number of stars), link to Tripadvisor, and more details. Use Google to find the hotel homepage.



Sponsoring Opportunities and Exhibition

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